

REMARKS

The amendment to claim 1 is supported by the original disclosure at paragraph [0015]. New claim 31 is supported by the original disclosure at paragraph [0034]. Applicants submit that the amendments do not add any new matter to the disclosure.

Regarding the objection to use of the terms local and proximate, applicants submit that Figures 4 through 8 adequately illustrate the scope of these terms and that revision of the specification such that further definition or clarification should not be necessary. Applicants further submit the amendment of the claims to refer to patterns on an integrated circuit substrate provide further context for the understanding of these terms.

The invention centers on methods of locally altering a feature of an existing pattern on an integrated circuit substrate. The invention achieves this result with minimal side reaction by use of a combination of local chemical delivery with activation energy provided by illumination. This combination enables precise alteration without adverse impact on the remaining portions of the pattern.

Goodman et al. (US 6316153) discloses a fabrication process using a photopolymerizable precursor and a probe tip photon source whereby a polymer structure is created on a substrate. Goodman et al. does not disclose or suggest the alteration of an existing pattern on an integrated circuit substrate.

Dykhno et al. (US 6388227) discloses a combined laser and plasma-arc welding process. Dykhno et al. does not disclose or suggest the alteration of an

existing pattern on an integrated circuit substrate. Applicants note that the arc welding temperatures would be too high for use on an integrated substrate. Also, the nozzle dimensions disclosed in col. 11, line 25 -36 are not suitable for editing patterns on an integrated circuit substrate.

Mirkin et al. (US 2002/0063212) discloses use of an AFM tip to direct molecules to a silver substrate. Mirkin et al. does not disclose or suggest the alteration of an existing pattern on an integrated circuit substrate. Applicants submit that an SPM/AFM tip is substantially different in nature compared to the probe used by Goodman et al. such that one of ordinary skill in the art would not have viewed their teachings as combinable. In any event, the combination of Goodman et al. with Mirkin et al. would still not result in the the alteration of an existing pattern on an integrated circuit substrate in as much as neither reference discloses that concept.

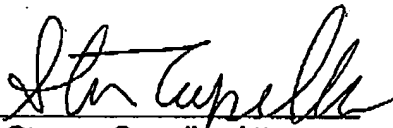
Martin et al. discloses illumination of a probe tip to create photon scattering. Martin et al. does not disclose or suggest the alteration of an existing pattern on an integrated circuit substrate. The combination of Martin et al. with Goodman et al. would still not result in the the alteration of an existing pattern on an integrated circuit substrate.

Izadpanah et al. (US 6735398) discloses a method of generating various pulsed waveforms. Izadpanah et al. does not disclose or suggest the alteration of an existing pattern on an integrated circuit substrate. The combination of Goodman et al. with Dykhno et al. and Izadpanah et al. would still not result in the the alteration of an existing pattern on an integrated circuit substrate in as much as none of these references discloses that concept. Similarly, the combination of Dykhno et al. and Izadpanah et al. would still not result in the the alteration of an existing pattern on an integrated circuit substrate.

For the above reasons, applicants submit that the claims are patentable and that the application is in condition for allowance. Such allowance is earnestly and respectfully solicited.

Respectfully submitted,

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